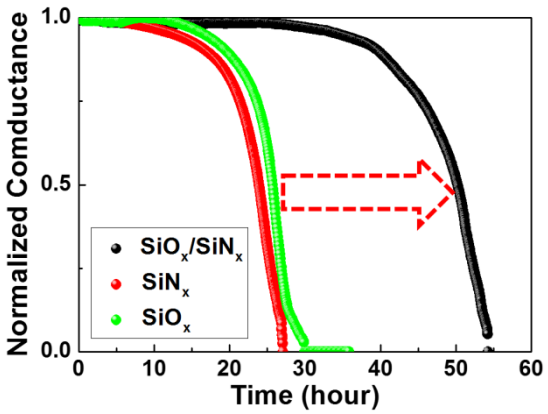
Table 1. Ca oxidation time and WVTR of PEALD SiOx (40 nm), SiNx (40 nm) single layer and SiOx/SiNx (10/40 nm) multilayer.

	SiOx	SiNx	SiOx/SiNx
Time (hour)	**29.9**	**27.1**	**54.3**
WVTR (g/m^2 day)	**7.05×10^{-3}**	**8.53×10^{-3}**	**3.79×10^{-3}**

Figure 1. Representative Ca-test results of single PEALD SiOx (40 nm), SiNx (40 nm) single layer and SiOx/SiNx (10/40 nm) multilayer.



[1] Jin-Seong Park, Heeyeop Chae, Ho Kyoon Chung and Sang In Lee, Thin film encapsulation for flexible AM-OLED: a review, Semicond. Sci. Technol. 26 (2011) 034001 (8pp)

[2] Won Min Yun, Jaeyoung Jang, Sooji Nam, Lae Ho Kim, Sang Joon Seo, and Chan Eon Park, Thermally Evaporated SiO Thin Films As a Versatile Interlayer for Plasma-Based OLED Passivation, ACS Appl. Mater. Interfaces 2012, 4, 3247−3253

[3] N. Kim, W. J. Potscavage, Jr., B. Domercq, B. Kippelen, and S. Graham, A hybrid encapsulation method for organic electronics, APPLIED PHYSICS LETTERS 94, 163308 (2009)

[4] J. Meyer, D. Schneidenbach, T. Winkler, S. Hamwi, T. Weimann, P. Hinze, S. Ammermann, H.-H. Johannes, T. Riedl, and W. Kowalsky, Reliable thin film encapsulation for organic light emitting diodes grown by lowtemperature atomic layer deposition, APPLIED PHYSICS LETTERS 94, 233305 (2009)

[5] E. Langereis, M. Creatore, S. B. S. Heil, M. C. M. van de Sanden, and W. M. M. Kessels, Plasma-assisted atomic layer deposition of Al2O3 moisture permeation barriers on polymers, APPLIED PHYSICS LETTERS 89, 081915 (2006)

[6] Arrelaine A. Dameron, Stephen D. Davidson, Beau B. Burton, Peter F. Carcia, R. Scott McLean, and Steven M. George, Gas Diffusion Barriers on Polymers Using Multilayers Fabricated by Al2O3 and Rapid SiO2 Atomic Layer Deposition, *J. Phys. Chem. C* 2008, *112,* 4573-4580